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APPLICATION NO.	FIL	ING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/697,045	10/31/2003		Takashi Kuroi	244521US-2 DIV 8375	
22850	7590	10/19/2004		EXAMINER	
OBLON, S 1940 DUKE	•	CCLELLAND	POMPEY, RON EVERETT		
	DRIA, VA 22314			ART UNIT	PAPER NUMBER
	,			2812	

DATE MAILED: 10/19/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
	10/697,045	KUROI ET AL.				
Office Action Summary	Examiner	Art Unit				
	Ron E Pompey	2812				
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence address				
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply If NO period for reply is specified above, the maximum statutory period we Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	6(a). In no event, however, may a reply be timwithin the statutory minimum of thirty (30) days ill apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication. O (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on 26 Ju	<u>ly 2004</u> .					
2a)⊠ This action is FINAL . 2b)☐ This						
3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is						
closed in accordance with the practice under E	x parte Quayle, 1935 C.D. 11, 45	33 O.G. 213.				
Disposition of Claims						
4) Claim(s) 10 and 13-20 is/are pending in the ap	plication.					
4a) Of the above claim(s) is/are withdraw	n from consideration.					
5) Claim(s) is/are allowed.						
6)⊠ Claim(s) <u>10 and 13-20</u> is/are rejected.	6) Claim(s) 10 and 13-20 is/are rejected.					
7) Claim(s) is/are objected to.						
8) Claim(s) are subject to restriction and/or	election requirement.					
Application Papers		in property of the second of t				
9) The specification is objected to by the Examine	r.					
10) ☐ The drawing(s) filed on is/are: a) ☐ acce	The drawing(s) filed on is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.					
Applicant may not request that any objection to the	drawing(s) be held in abeyance. See	e 37 CFR 1.85(a).				
Replacement drawing sheet(s) including the correcti						
11)☐ The oath or declaration is objected to by the Ex	aminer. Note the attached Office	Action or form PTO-152.				
Priority under 35 U.S.C. § 119						
 12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the priority application from the International Bureau 	s have been received. s have been received in Applicati ity documents have been receive	on No				
* See the attached detailed Office action for a list of the state of t	of the certified copies not receive	ed.				
1) X Notice of References Cited (PTO-892)	4) Interview Summary					
2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date	Paper No(s)/Mail Da 5) Notice of Informal P 6) Other:	ate ratent Application (PTO-152)				

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DETAILED ACTION

Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 10 and 13- 20 are rejected under 35 U.S.C. 103(a) as being unpatentable over Krivokapic et al. (US 6,087,208).

Krivokapic discloses the limitations of:

- a) forming a structure (40 and 50, fig. 10) on a main surface of a substrate in an area in which a gate electrode is formed later;
- (b) forming source/drain regions (78 and 80, fig. 11) in said main surface of said substrate in an area in which said structure is not formed;
- (c) forming a first insulating film (190, fig. 15) on said main surface of said substrate in an area in which said structure is not formed;
 - (d) after said step (c), removing said structure (fig. 17);
- (e) forming a second insulating film on the construction obtained by said step (d) and etching said second insulating film by an anisotropic etching whose etching rate is higher in depth direction of said substrate to form sidewalls (194 and 196, fig. 18) on sides of said first insulating film; and

forming said gate electrode (220, fig. 20) to fill an inversely tapered recessed part formed by sides of said sidewalls and an upper surface of said gate insulating film; and

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(f) forming a gate insulating film (210, fig. 19) composed of a third insulating film on said main surface of said substrate in an area in which said first insulting film and said sidewalls are not formed (col. 15, In. 30 – col. 16, In. 43).

wherein. in said step (a). said structure is formed by stacking a first film (40, fig. 8) composed of a material which is different from that of said second insulating film and a second film(50, fig. 10) composed of a material which is different from that of said first insulating film in this orders and said step (d) comprises the steps of; (d-1) between said step (c) and said step (e), removing said second film with said first film left unremoved(fig. 17) and (d-2) between said step (e) and said step (f), removing said first film by a etching.

Krivokapic does not disclose the claimed limitation(s) of:

Anisotropic or wet etching.

However,

Krivokapic discloses using any suitable etchants for removal of the dummy gate and the unmasked portion of the thin gate oxide, in column(s) 8, line(s) 19-17.

Therefore, it would have been obvious to one of ordinary skill in the art at the time of the invention to use anisotropic or wet etching, because these are common ways to etch materials in the semiconductor art.

Response to Arguments

3. Applicant's arguments with respect to claims 10 and 13-20 have been considered but are most in view of the new ground(s) of rejection.

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Conclusion

4. Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Ron E Pompey whose telephone number is (571) 272-1680.

Ron Pompey

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October 18, 2004

Supervisory Patent Examiner Technology Center 2800